



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of) Box AF
)
Johnson et al.) Group Art Unit: 2851
)
Application No.: 09/610,239) Examiner: Nguyen, Hung
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Filed: July 5, 2000) Confirmation No.: 4991
)
For: IN VACUUM EXPOSURE SHUTTER)

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AMENDMENT AFTER FINAL

Assistant Commissioner for Patents
Washington, D.C. 20231

Sir:

Applicants submit the following Amendment After Final in response to the Office Action dated May 15, 2002. Formal drawings are also submitted herewith.

IN THE CLAIMS:

Please amend Claims 1 and 14 to read as follows:

1. (Twice Amended) An exposure device comprising:
a source of radiation that generates an energy beam;
a shutter that includes (i) a frame defining an aperture toward which the energy beam is directed and (ii) a plurality of blades that are secured to the frame wherein each blade does not move relative to the other blades; and
means for rotating the frame of the shutter to cause the plurality of blades to intercept or allow the energy beam to travel through the aperture wherein the positions of the individual blades remain fixed relative to each other.
14. (Twice Amended) A method of patterning a substrate through controlled exposure of the substrate in a vacuum system which comprises the steps of:
generating radiation comprising an energy beam;